

Spectrometric Studies of Selected Nitrocompounds Using Laser-Induced Photofragmentation/Photoionization at 193 nm

Rosario C. Sausa Josef B. Simeonsson George W. Lemire

ARL-TR-628

November 1994



19950124 015

DTIC QUALITY INSPECTED 2

APPROVED FOR PUBLIC RELEASE; DISTRIBUTION IS UNLIMITED.

NOTICES

Destroy this report when it is no longer needed. DO NOT return it to the originator.

Additional copies of this report may be obtained from the National Technical Information Service, U.S. Department of Commerce, 5285 Port Royal Road, Springfield, VA 22161.

The findings of this report are not to be construed as an official Department of the Army position, unless so designated by other authorized documents.

The use of trade names or manufacturers' names in this report does not constitute endorsement of any commercial product.

REPORT DOCUMENTATION PAGE

Form Approved
OMB No. 0704-0188

Public reporting burden for this collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searching existing data sources, gathering and maintaining the data needed, and completing and reviewing the collection of information. Send comments regarding this burden estimate c: any other aspect of this collection of information, including suggestions for reducing this burden, to Washington Headquarters Services, Directorate for Information Operations and Reports, 1215 Jefferson Davis Highway, Suite 1204, Arlington, VA 222024302, and to the Office of Management and Buddet, Paperwork Reduction Project (10704-0188), Washington, DC 20503.

collection of information, including suggestion. Davis Highway, Suite 1204, Arlington, VA 222					
1. AGENCY USE ONLY (Leave bla	· ·	· · · -	3. REPORT TYPE AN		COVERED
4. TITLE AND SUBTITLE	Novemb	er 1994	Final. Aug 93 - I		DING NUMBERS
Spectrometric Studies of Sele Photofragmentation/Photoionia	•	ds Using Lad	ser-Induced	-	
6. AUTHOR(S)			PR:	1L161102AH43	
Rosario C. Sausa, Josef B. Sir	neonsson, and Geo	rge W. Lem	ire		
7. PERFORMING ORGANIZATION F	IAME(S) AND ADDRI	ESS(ES)			DRMING ORGANIZATION RT NUMBER
U.S. Army Research Laborato ATTN: AMSRL-WT-PC	•				
Aberdeen Proving Ground, M	D 21005-5066				
9. SPONSORING / MONITORING AC	iENCY NAME(S) AND	ADDRESS(E	5)		ISORING/MONITORING NCY REPORT NUMBER
U.S. Army Research Laborato ATTN: AMSRL-OP-AP-L	гу			ARI	L-TR-628
Aberdeen Proving Ground, M	D 21005-5066				
11. SUPPLEMENTARY NOTES				 	
Mr. Simeonsson and Mr. Lem	•	postdoctoral	research associates.		
12a. DISTRIBUTION / AVAILABILITY	STATEMENT			12b. DIS	TRIBUTION CODE
Approved for public release; of	listribution is unlim	ited.			
13. ABSTRACT (Maximum 200 work	ds)				
A new method for detect demonstrated using one color is photolytically fragment the tar. The production of NO is hypot yielding NO in its $X^2\Pi$ electromolecules is accomplished by $X^2\Pi$ (7,0), and/or $D^2\Sigma^+ <-X^2\Pi$ molecular beam time-of-flight (ppb) level for NO, NO ₂ , Continuous trinitrotoluene (TNT). Under nitrotoluene and meta-nitrotoluene photoionization mass spectra.	aser photofragmenta get molecules in a hesized to result fro onic ground state a resonance-enhanced ² II (0,1) bands at apparatus. Limits ² H ₃ NO ₂ , dimethyln effusive beam expe	ation/fragment collision-freem a combinate other imultiphoto 193 nm. To detection a combinate of detection and the collision of detection of detection of detection and the collision of detection of det	nt ionization spectrometric environment and ionication of two NO_2 unimore in its $A^2\Sigma^+$ excited stantial ionization processes value analytical utility of range from the parts-populations, ortho- and manditions, discrimination	ry. An Arize the charlecular fra ate. Ionize ia their Afthis met ex-million eta-nitroto between	F laser is employed to both aracteristic NO fragments. agmentation pathways, one vation of ground state NO $^2\Sigma^+ <- X^2\Pi$ (3,0), $B^2\Pi <-$ thod is demonstrated in a (ppm) to parts-per-billion bluene, nitrobenzene, and structural isomers, ortho-
14. SUBJECT TERMS					15. NUMBER OF PAGES
	20 3			1	22
photofragment spectroscopy, la ionization (REMPI), ArF excir		n, resonance	-ennanced multiphoton		16. PRICE CODE
17. SECURITY CLASSIFICATION OF REPORT	18. SECURITY CLASS OF THIS PAGE	SIFICATION	19. SECURITY CLASSIFIC OF ABSTRACT	CATION	20. LIMITATION OF ABSTRACT
UNCLASSIFIED	UNCLASSIFIED		UNCLASSIFIED		SAR

INTENTIONALLY LEFT BLANK.

ACKNOWLEDGMENTS

The authors thank Drs. S. Balusu, U.S. Army Research, Development, and Engineering Center, and R. Pesce-Rodriquez, U.S. Army Research Laboratory (ARL), for providing some of the sample nitrocompounds, and Dr. M. Schroeder (ARL) for helpful discussions regarding the rearrangements of *ortho-* and *meta-*nitrotoluenes. Support from the NAS/NRC Postdoctoral Research Program (JBS & GWL), the ARL Combustion and Environmental Mission Program (RCS), and the PIF/OSD Capital Investment Program (RCS) is gratefully acknowledged.

Accesion For			
4	CRA&I	À	
Unann	DTIC TAB Unannounced Justification		
	By Distribution /		
Availability Codes			
Dist	Avail and / or Special		
A-1			

INTENTIONALLY LEFT BLANK.

TABLE OF CONTENTS

		Page
	ACKNOWLEDGMENTS	ii
	LIST OF FIGURES	vi
	LIST OF TABLES	vi
1.	INTRODUCTION	1
2.	EXPERIMENTAL	2
3.	RESULTS/DISCUSSION	5
4.	CONCLUSIONS	14
5.	REFERENCES	15
	DISTRIBUTION LIST	17

INTENTIONALLY LEFT BLANK.

LIST OF FIGURES

Figure		Page
1.	Schematic diagram of the salient features of the experimental apparatus	3
2.	Time-of-flight spectrum of a molecular beam of DMNA sampled from an atmosphere of argon	6
3.	Potential energy diagram of NO ₂ and NO revealing the resonance-enhanced multiphoton ionization scheme for the detection of NO at 193 nm	9
4.	Time-of-flight spectra of <i>ortho</i> -nitrotoluene (A) and <i>meta</i> -nitrotoluene (B) obtained under effusive sampling using 193-nm radiation	12
	LIST OF TABLES	
<u>Table</u>		Page
1.	Limits of Detection of Selected Nitrocompounds Using ArF Laser Photofragmentation/Ionization Spectrometry	7
2	Palative Intensities of Ions for Ortho- and Mata-nitrotoluene	13

INTENTIONALLY LEFT BLANK.

1. INTRODUCTION

Trace detection of energetic materials (EMs) is a difficult analytical problem that has important applications in aviation security, forensics, and military mine countermeasures (Fainberg 1992; Reutter, Buechele, and Rudolph 1983; and Haung, Kolaitis, and Lubman 1987). The challenge is to develop a vapor phase detector for these compounds that has sufficiently high levels of sensitivity and selectivity, and can operate in real time. This is a formidable challenge since most EMs are low in volatility and thermally labile. Methods that are currently used to detect EMs in the vapor phase include ion mobility spectrometry (IMS) and mass spectrometry coupled with gas chromatography (Fainberg 1992). By comparison, optical detection is difficult to accomplish because of weak and featureless absorptions, and the susceptibility of large molecules to undergo nonradiative relaxation processes including fragmentation. An alternative approach to direct spectroscopic detection is photofragmentation/photoionization (PF/PI) spectroscopy. In this technique, characteristic fragments generated from the photolysis of the parent molecule are probed spectroscopically. For representative studies, see Rodgers, Asai, and Davis (1980); Schendel, Hohmann, and Wehry (1987); Lee et al. (1992); Sausa, Alfano, and Miziolek (1987); Clark et al. (1992); Marshall et al. (1992); Oldenborg and Baughcum (1986); Schendel et al. (1990); and Schendel and Wehry (1988); and references therein. These smaller fragments include atoms, diatomics, and triatomics, which have relatively sharp and strong spectral features, and can readily be detected by prompt emission, laser-induced fluorescence (LIF), or multiphoton ionization (MPI) spectrometry techniques.

Common to most EMs is the NO_2 functionality which is easily removed by excitation in the 190–250 nm region of the ultraviolet (UV) spectrum (Smit 1991). The NO2 molecule can itself be detected or further fragmented to form NO, which is detected by LIF or resonance-enhanced multiphoton ionization (REMPI) using the strong $A^2\Sigma^+$ ($\nu'=0$) <- $X^2\Pi$ ($\nu''=0$) transition at 226 nm for excitation. Recently, we reported the demonstration of a new method of detecting NO_2 —containing compounds based on the photolysis of the parent molecule and subsequent REMPI of the NO fragment using one laser tuned to 226 nm (Lemire, Simeonsson, and Sausa 1993). This method is both sensitive and selective, and achieves gas phase concentration limits of detection (LOD) in the parts per billion (ppb) to parts per million (ppm) range for selected compounds, including trinitrotoluene (TNT) and hexahydro-1,3,5-trinitro-1,3,5,-triazine (RDX).

A significant drawback of the method used in our previous work is the complexity of the instrumentation which includes an excimer-pumped dye laser system with second harmonic generation.

Instead of a dye laser, it would be preferable to use a nontunable laser source which can both photofragment and ionize the NO fragment. The ArF laser operating at 193 nm is a good candidate for this approach since it is an efficient photolysis source useful for generating the NO₂ fragment (Schendel, Hohmann, and Wehry 1987), and can also operate as a REMPI source for NO molecules exciting several transitions in the $A^2\Sigma^+ \leftarrow X^2\Pi$ (3,0) and $B^2\Pi \leftarrow X^2\Pi$ (7,0) bands near 193 nm (Robie, Buck, and Bischel 1990) through higher rotational levels. In addition to ground state resonances, the ArF laser output can excite transitions in the $D^2\Sigma$ (v'=0) <- $X^2\Pi$ (v"=1) band (J"=19.5-44.5) (Robie, Buck, and Bishel 1990; Wodtke et al. 1988).

In the current study, selected nitrocompounds are detected with the use of an ArF laser as the photofragmention source for target molecules and also as the REMPI source for NO fragments. The analytical utility of this method is demonstrated on a number of compounds including NO, NO₂, dimethylnitramine (DMNA), nitromethane, nitrobenzene, *ortho-* and *meta-*nitrotoluene, and TNT employing molecular beam sampling with mass spectrometric detection. Limits of detection are reported and compared to those obtained previously by other methods. The photodissociation and ionization mechanisms at 193 nm are also discussed. Discrimination between different NO₂-containing compounds is demonstrated using two structural isomers under effusive beam conditions. Mass spectra containing characteristic fragmentation is observed for each isomer.

2. EXPERIMENTAL

The molecular beam/time-of-flight mass spectrometer system used in this study has been described in a previous publication (Lemire, Simeonsson, and Sausa 1993). A schematic diagram of the salient features is shown in Figure 1. Briefly, sample vapors were introduced as minor species in Ar (99.995%, Potomac Gases), nitrogen, or air (ARL Post Gases) which served as the expansion gas. Gas phase concentrations were calculated using the vapor pressures of the compounds at room temperature. The mixtures were expanded from a pulsed supersonic valve (R. M. Jordan and Associates) into a vacuum chamber, pumped by a turbomolecular pump, which maintained an average pressure of 10⁻⁴ Torr. A skimmer placed 2 cm from the nozzle transmitted a molecular beam into a second high-vacuum chamber (10⁻⁶ Torr). The molecular beam traversed the ionization region of a reflectron-type (Wiley-McLaren design) time-of-flight mass spectrometer (R. M. Jordan and Associates) whose flight tube was oriented perpendicular to the direction of the molecular beam. Ions produced in the ionization region were transmitted into the flight tube by acceleration plates biased at 1,500 V. Effusive beam sampling was

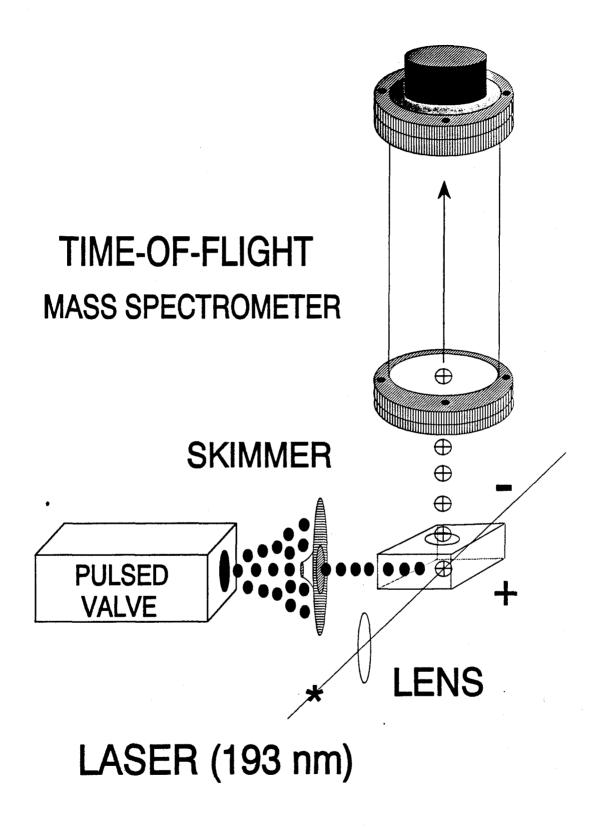


Figure 1. Schematic diagram of the salient features of the experimental apparatus.

accomplished by placing a small amount of the compound of interest in a quartz tube connected by a Cajon fitting to a needle valve on the ionization chamber. Sample vapor pressures in the chamber were regulated by the needle valve.

An excimer laser (Lambda Physik EMG 150C) operating at 193 nm with ArF was used for photolysis and ionization. The laser beam was aperatured to 10 mm in diameter, and transmitted into the vacuum chamber through MgF_2 windows into the center of the ionization region. In this region, the laser beam was both perpendicular to the molecular beam and the flight tube. A quartz lens (250 mm) external to the vacuum chamber was used for focusing to increase the laser fluence in the sample ionization region. Pulse energies of the ArF laser were nominally 1 to 1.5 mJ in the photolysis region for all of the measurements. A maximum laser fluence of 10^{22} photons/cm² was calculated using a focal spot area estimated to be 1×10^{-7} cm².

Operation of the pulsed supersonic valve and the laser was synchronized and controlled by a precision delay generator (Stanford Research Systems #DG535). Time-of-flight mass spectra were acquired by a 125-MHz digital oscilloscope (LeCroy 9400) that was interfaced to a PC-AT for storage. Quantitative measurements were performed by collecting the NO⁺ signal with a boxcar (Stanford Research Systems 255) whose gate was adjusted to the time of arrival of the NO⁺ fragment. The boxcar was also interfaced through an A/D converter to the PC-AT for data storage and analysis.

Calibration of the time-of-flight mass spectrometer response was accomplished using a standard NO in Ar mixture. The times-of-arrival NO⁺ and Ar⁺ ion signals allowed the determination of unknown masses through the following relationship (Wiley and McLaren 1955; Karataev, Mamyrin, and Shmikk 1972).

$$\frac{\mathrm{m}_1}{\mathrm{m}_2} = \left(\frac{\mathrm{t}_1}{\mathrm{t}_2}\right)^2 \tag{1}$$

Samples of DMNA were obtained from ARDEC, *ortho-* and *meta-*nitrotoluenes from ARL, and nitrobenzene and TNT from Eastman-Kodak. Nitromethane (spectrophotometric grade) was obtained from Mallinckrodt. NO was obtained from Union Carbide at 0.1% in Ar. NO₂ was obtained from Matheson at 6.20 ppm in air.

3. RESULTS/DISCUSSION

Selected nitrocompounds have been studied using the one laser photofragmentation/photoionization method. Shown in Figure 2 is a typical time-of-flight ion spectrum obtained at 193 nm for a molecular beam of DMNA in Ar. DMNA is a simulant molecule for the primary explosives RDX and octahydro-1,3,5,7-tetranitro-1,3,5,7-tetrazocine (HMX). In results similar to those for excitation at 226 nm (Lemire, Simeonsson, and Sausa 1993), the ion spectra of all the compounds at 193 nm are characterized by a strong ion signal whose time-of-arrival corresponds to a mass-to-charge ratio of 30. The molecular weight of NO⁺, and the high intensity of the NO⁺ signal and near exclusion of all other ion signals are indicative of a resonant enhancement of the fragmentation and/or ionization processes, and demonstrate the high selectivity of the method when 193-nm excitation is used. As a result of the higher laser fluences used at 193 nm, buffer gases such as Ar, N₂, and air-produced Ar⁺, N₂⁺, and other ion signals necessitating mass spectrometric detection. It is interesting to note that no ion signal was observed for NO₂⁺. The absence of NO₂⁺ signals is consistent with our previous studies, and is indicative of the rapid predissociation of excited NO₂ which prevents detectable ionization of the molecule.

Concentration limits of detection (LODs) measured for each compound studied are reported in Table 1. They are based on the measurement of the NO^+ ion signal and range from the ppb to ppm levels in 1 atm of Ar prior to introduction into the sampling apparatus. The analytical sensitivity is dependent on a number of parameters including: (1) the absorption cross section of the parent molecule at 193 nm, (2) the efficiency of photofragmentation of the parent molecule at 193 nm to yield NO in both its ground ($X^2\Pi$) and electronically excited ($A^2\Sigma^+$) states, and (3) the ionization cross section at 193 nm for NO in the above-mentioned states. Shown for comparison are LODs for the same compounds using the same apparatus with 226-nm excitation. The linear dynamic range at 193 nm extends three orders of magnitude for the detection of NO and over two orders for the detection of nitromethane. For most compounds, the upper bound of the linear dynamic range was limited by the vapor pressure of the compound.

It is useful to compare the results obtained in this study with those of similar studies. Employing photfragmentation/fluorescence spectrometry (PFFS), Schendel, Hohmann, and Wehry (1987) have reported an LOD for nitromethane of 4.2×10^9 molecules/cm³ and similar order of magnitude values for nitriles, amines, and alkenes. Wodtke et al. (1988) estimated an LOD of 1 ppb for LIF measurements of NO in a flame using an ArF laser which corresponds to a number density of 4×10^9 molecules/cm³. With an estimated gas throughput of 0.041 Torr-cm³, the LOD of 180 ppb for nitromethane in this study

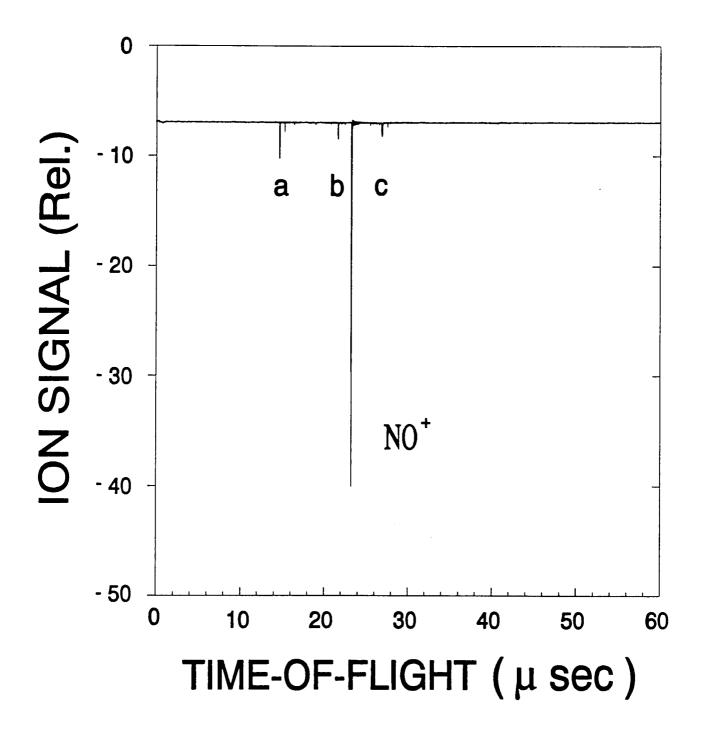


Figure 2. Time-of flight spectrum of a molecular beam of DMNA sampled from and atmosphere of argon.

This spectrum is an average of ten spectra collected in 1 second using 193-nm radiation as the photolysis source. Features A, B, and C are assigned to C⁺, C₂⁺, and Ar⁺, respectively.

Table 1. Limits of Detection of Selected Nitrocompounds Using ArF Laser Photofragmentation/Ionization Spectrometry

Compound	Limits of Detection (ppm ^a in Ar) 193 nm	Limits of Detection (ppm ^a in Ar) 226 nm
NO	1.2	0.008 ^b
NO ₂	0.50	0.24 ^b
CH ₃ NO ₂	0.18	1.0 ^b
DMNA	0.51	0.45 ^b
Nitrobenzene	0.49	2.4 ^b
Ortho-nitrotoluene	0.12	15
Meta-nitrotoluene	0.10	36
TNT ^c	0.21	1.7

^a Concentrations of species based on vapor pressures reported in Dobratz (1981) and CRC Handbook of Chemistry and Physics (1986).

corresponds to a number density of 1×10^9 molecules/cm³ in the probe region. Clark et al. (1993) have estimated an LOD of 1.1×10^9 molecules/cm³ for nitrobenzene using a similar photofragmentation ionization at 226.3 nm. In the present study, an LOD of 0.49 ppm for nitrobenzene corresponds to a number density of 3×10^9 molecules/cm³.

Further inspection of the results in Table 1 shows important differences in the trends of the detection limits at 193 nm and 226 nm. In particular, the LODs for individual compounds at different wavelengths suggest differences in the photofragmentation and/or photoionization mechanisms. For example, the LOD for NO is 8 ppb at 226 nm, and 1.2 ppm at 193 nm. At 226 nm, the laser excitation wavelength is resonant with the strong $A^2\Sigma^+$ (v'=0) <- $X^2\Pi$ (v''=0) transition, which is a highly efficient means of ionizing ground state NO molecules. In a supersonic expansion of NO, the vast majority of molecules are in low rotational energy levels of the vibrational ground state and, as a result, the REMPI of NO at this wavelength is highly sensitive. In contrast, the LOD for NO is over two orders of magnitude greater at 193 nm than at 226 nm, even despite higher laser energies (1 to 1.5 mJ at 193 nm vs. 100 μ J at 226 nm). This observation is due to the fact that the 193-nm excitation is resonant with transitions from

b Reported previously in Lemire, Simeonsson, and Sausa (1993).

^c Results for TNT obtained using an effusive sample source.

weakly populated rotational states in the vibrational ground state in the A<-X and B<-X bands of NO. Furthermore, the spectral energy density of the ArF laser, which has a relatively large spectral bandwidth (100 cm⁻¹), is approximately 60 times less than the dye laser radiation. Both of these factors contribute to a low overall photoionization rate; thus, a lower sensitivity for NO detection.

By contrast, the relative sensitivities for large molecules at 193 nm are in general higher than those at 226 nm, as shown in Table 1. The increased sensitivity may be explained in terms of two factors: (1) the photofragmentation efficiency for the larger molecules is usually higher at shorter wavelengths, and (2) following photofragmentation, a larger fraction of the nascent NO fragment population distribution is resonant with the 193 nm radiation as compared to the 226 nm radiation. The latter factor is supported by studies of the population distributions of the photofragments of nitromethane at 193 nm (Butler et al. 1983; and Moss, Trentelman, and Houston 1992), which indicate that up to 10% of the NO produced by unimolecular dissociation of the NO₂ photofragment may be in v=1 in the $X^2\Pi$ state. As noted earlier, high sensitivity LIF measurements of vibrationally excited NO have been reported at 193 nm (Wodtke et al. 1988) by way of the $D^2\Sigma$ (v'=0)<- $X^2\Pi$ (v''=1) band. Presumably these transitions are also effective as first steps in a 1+1 REMPI mechanism for the production of NO⁺.

The enhanced sensitivity for the NO photofragment at 193 nm also indicates that the photofragmentation and ionization mechanisms may be different at 193 nm and 226 nm. In order to understand the dynamics of the fragmentation and ionization processes at 193 nm, it is useful to consider the potential energy level diagrams of NO and NO_2 shown in Figure 3. Ground state NO molecules have several absorption resonances with the output of the ArF excimer laser (Robie, Buck, and Bishel 1990; Wodtke et al. 1988), which correspond to high rotational lines of the A<-X and B<-X bands. The multiphoton ionization of NO by a 1+1 REMPI mechanism is possible by these transitions; however, it is inefficient since these high rotational energy levels are unlikely to be significantly populated in a supersonically cooled expansion. Following absorption at 193 nm, NO_2 molecules have sufficient energy to predissociate primarily into $NO(X^2\Pi)$ and $O(^1D)$ atoms (Butler et al. 1983; Moss, Trentelman and Houston 1992). The nascent NO fragments have a range of internal energies compared to the jet-cooled NO molecules and, as a result, more will be ionized by the 1+1 REMPI processes. This observation is manifested in the measured LOD's for NO and NO_2 which are 1.2 and 0.5 ppm, respectively (see Table 1).

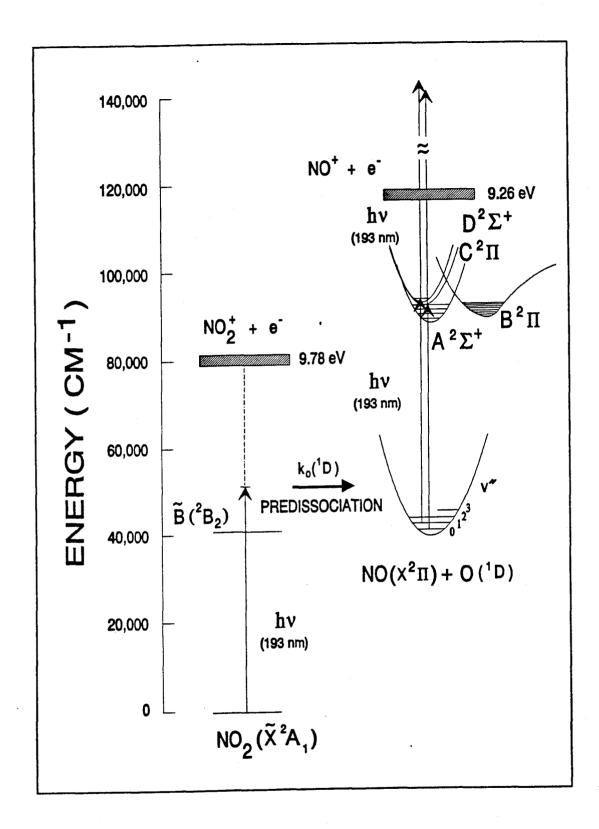


Figure 3. Potential energy diagram of NO₂ and NO revealing the resonance-enhanced multiphoton ionization scheme for detection of NO at 193 nm.

The mechanism by which NO^+ is produced from the ArF photofragmentation of R- NO_2 has not been yet determined. However, its formation is believed to result from both ground and electronically excited NO_2 , produced from the 193-nm excitation of R- NO_2 . This mechanism is inferred from previous studies on the photofragmentation dynamics of nitromethane at 193 nm (Butler et al. 1983; Moss, Trentelman, and Houston 1992). In one of these studies, Moss and co-workers employed multiphoton ionization spectroscopy and time-of-flight mass spectrometry to determine the nascent photofragment energy distributions of several of the products. Their study reveals that both $\mathrm{NO}(\mathrm{X})$ and $\mathrm{NO}(\mathrm{A})$ are produced from the parent molecule by a two-channel dissociation. The major channel produces CH_3 and its companion photoproduct NO_2 , formed in its electronically excited $\mathrm{\tilde{A}}^2\mathrm{B}_2$ state. The electronically excited NO_2 has sufficient internal excitation to further dissociate to $\mathrm{NO}(\mathrm{X})$ and O as follows:

$$NO_2 (\tilde{A}^2 B_2) \longrightarrow NO (X^2 \Pi) + O (^1 D)$$
 (2)

Under our experimental conditions, multiphoton ionization of the ground state NO is then possible by transitions in the A, B and D <-X bands. In the minor channel, the NO₂ photofragment is produced in its excited \tilde{B}^2B_2 state. The subsequent absorption of an additional 193 nm photon results in its photodissociation yielding NO(A² Σ^+) and O(³P). This channel is represented by the following reaction:

$$NO_2(\tilde{B}^2B_2) \frac{hv}{193nm} > NO(A^2\Sigma) + O(^3P)$$
 (3)

Photoionization of the NO at 193 nm is direct from this state and requires one less photon than the ionization of ground state NO molecules. If these two channels are viable for the other nitrocompounds studied, then the sum of the contributions from the these two channels and that from ground state NO_2 photofragments accounts for the enhanced sensitivity observed for NO fragments at 193 nm.

In addition to the sensitivity of the photofragmentation/photoionization approach, it is interesting to note that ArF laser excitation and effusive source sampling have been used to distinguish structural isomers of nitrotoluene by their mass spectral fragmentation patterns. In this study, it was observed that the relative intensity of the various ions in a given spectrum were highly dependent on the focusing characteristics of the laser excitation. The largest ion signals for the NO photofragment were observed when the laser fluence was the highest. The only other ion signal of similar intensity was attributed to

C⁺, which results from a two photon resonance-enhanced excitation process of the metastable carbon atom via its well-known (Sausa, Alfano, and Miziolek 1987; Döbele and Rückle 1982, 1992) (2p3s ¹P₁<-2p² ¹D₂) transition at 193.1 nm. As the laser fluence was reduced, the NO⁺ and C⁺ signals decreased dramatically, and other ion signals appeared. These signals corresponded to the parent ions and larger fragments characteristic of the parent molecules. Previous studies of the ultraviolet photofragmentation and ionization of nitrobenzene using effusive sampling and a tunable dye laser in the 245–260 nm range have shown similar intensity-dependent results (Clark et al. 1992).

Shown in Figures 4a and 4b are time-of-flight mass spectra of ortho-nitrotoluene (ONT) and metanitrotoluene (MNT), respectively, which illustrate the fragmentation and ionization of the molecules using an unfocused ArF laser as the excitation source and effusive sampling. These two molecules produce similar fragments but in different intensity ratios. The ArF excited spectra are similar to electron impact (EI) spectra, with the exception of enhanced signals for the NO⁺ species, and can be used to identify and differentiate these two isomers. Relative fragment peak intensities for ONT and MNT are given in Table 2. Readily identifiable masses include m/z=77 (phenyl group), 91/92 (tropylium or benzyl ion and the protonated forms) and 137 (nitrotoluene parent ion).

The ion peaks at m/z=77 and m/z=107 are noticeably more intense in the case of MNT. The m/z=107 is attributed to CH₃-C₆H₄-O, which is the result of a rearrangement of the parent molecule followed by the loss of NO. This rearrangement is well-known for nitro-containing aliphatic and aromatic hydrocarbons (Silverstein, Bassler, and Morrill 1991). This rearrangement is also rationalized by the different peak intensities for the two isomers. Steric effects by the adjacent methyl group can hinder the rearrangement in the case of ONT but are less important in the case of MNT. This same trend is observed in the electron impact mass spectra, m/z=107 ion intensity being of the lowest intensity for the *ortho*-isomer, of moderate intensity for the *meta*-isomer, and of greatest intensity for the *para*-isomer where the methyl and nitro groups are farthest apart.

The above results demonstrate that, under effusive conditions, identification of isomeric compounds may be accomplished by adjustment of the laser fluence to produce characteristic mass fragments. The potential for compound discrimination or even identification by this method is a significant prospect for the photofragmentation/photoionization approach. The current example of structural isomer differentiation illustrates how, in this case, sensitivity can be compromised in order to obtain enhanced selectivity. A similar trend was expected under atmospheric molecular beam conditions, but was not observed. At present, this difference is not well understood, and is under investigation.

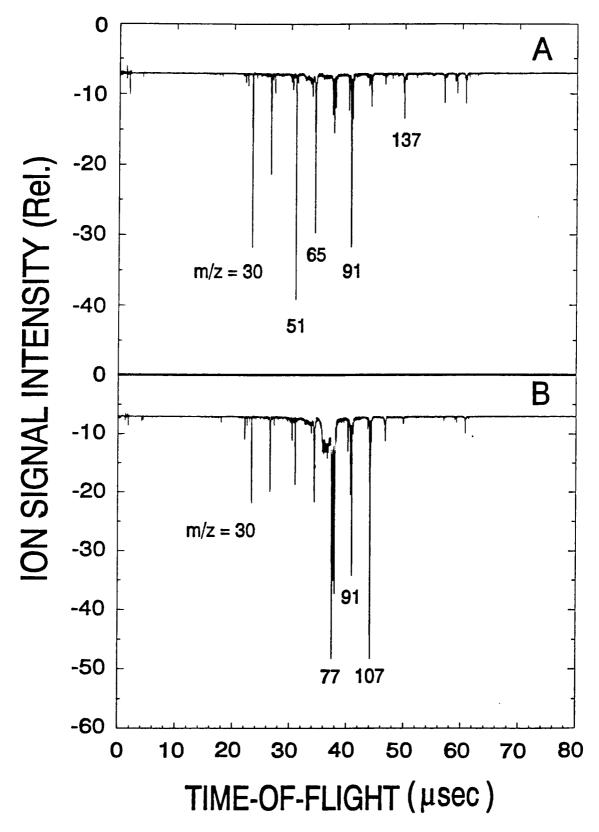


Figure 4. <u>Time-of-flight spectra of ortho-nitrotoluene (A)</u>, and meta-nitrotoluene (B) obtained under effusive sampling using 193-nm radiation.

Table 2. Relative Intensities of Ions for Ortho- and Meta-Nitrotoluene

m/z	Ortho-nitrotoluene (%) ^a	<i>Meta</i> -nitrotoluene (%) ^a
30	36	77
39	31	45
50	10	
51	28	100
65	36	71
77	100	26
91	13	77
92	66	-
107	100	15
120	9	<u> </u>
137	3	21

^a Intensities normalized to most intense mass peak.

Under atmospheric molecular beam conditions, significant improvement in the performance of the system could be achieved with changes in the sampling apparatus, whose current design is not optimal for trace analytical determinations. Improvements in the sample transmission efficiency from atmosphere into the photolysis/ionization region, estimated to be 0.02% in this study, could enhance the sensitivity greatly. Adsorption on the nozzle surface also lowers the sampling efficiency by removing a fraction of the sampled species. The ability to heat the nozzle to 150–200° C in order to avoid adsorption/condensation would be beneficial.

Temperature control of the nozzle would also reduce the amount of time spent flushing between samples, which was necessary to reduce background ion signals. A high temperature nozzle meeting this criterion has been designed and demonstrated previously for supersonic jet spectroscopy of polyaromatic hydrocarbons (PAHs) and would be ideal for this application (Imasaka, Okamura, and Ishibashi 1986). Another improvement to the system would be to increase the laser intensity to improve the signal-to-noise characteristics. The ArF laser intensity was insufficient to saturate the measured ion signal in this study and could be increased to saturation to increase the sensitivity and reduce pulse-to-pulse fluctuations in

the measured ion signals. Higher laser intensities would increase the sensitivity of the focal volume by increasing the number of species probed.

As these studies suggest, there are practical advantages to using an ArF laser rather than a dye laser for photofragment detection of NO_2 -containing compounds. An ArF laser can deliver up to several hundred millijoules per pulse at 193 nm, making it a much more effective photolysis source than any dye laser currently available. By having several spectral resonances with the NO molecule, the ArF laser is an effective REMPI source. In broadband operation, the ArF laser can simultaneously excite several transitions from the $X^2\Pi$ (v''=0,1) states which enhances photofragment detection. It can also produce electronically excited NO fragments in the $A^2\Sigma^+$ state which are readily photoionized. In contrast, a narrow bandwidth ($<0.1~{\rm cm}^{-1}$) dye laser generally restricts excitation to a single transition and rovibrational state. Other advantages of the ArF laser are that it is nontunable, rugged, and compact since it does not require laser dyes, dye cells, or delicate optical components. Although standard excimer laser technology does usually require gas handling equipment and the use of corrosive gases, excimer lasers can incorporate sealed discharge chambers allowing simplified operation. Thus, it is believed that excimer lasers have better potential for remote and/or *in situ* applications of the photofragmentation/fragment ionization technique.

4. CONCLUSIONS

A new method for the trace detection of nitrocompounds has been demonstrated at atmospheric conditions. This method uses an ArF excimer laser to both photofragment the parent molecule and ionize the characteristic NO fragment, and a time-of-flight mass spectrometer for detection. The photolysis yields significant nascent population of NO in rotationally and possibly vibrationally excited ground states resonant with 193-nm radiation, resulting in efficient ionization of the NO photofragment species by REMPI processes. ArF excitation can also ionize NO, which is produced in its electronically excited $A^2\Sigma^+$ state from the photolysis of the NO₂ fragment, and thus enhance the observed ionization signals for NO photofragments. The analytical utility of this method has been demonstrated on a number of compounds including NO, NO₂, nitromethane, DMNA, *ortho*- and *meta*-nitrotoluenes, and TNT. The limits of detection range from 100 ppb for meta-nitrotoluene to 1.2 ppm for NO and compare favorably with those reported by other spectroscopic methods. Under effusive sampling conditions, the selectivity of the method has been demonstrated to be enhanced by reducing the laser fluence to increase the ionization of other fragments.

5. REFERENCES

Butler, L. J., D. Krajnovich, Y. T. Lee, G. Ondrey, and R. Bersohn. <u>Journal of Chemical Physics</u>, vol. 79, no. 4, p. 1708, 1983.

Clark, A., K. W. D. Ledingham, A. Marshall, and R. P. Singhal. Spectrochimica Acta, vol. 47B, p. 799, 1992.

Clark, A., K. W. D. Ledingham, A. Marshall, J. Sander, and R. P. Singhal. To appear in Analyst, 1993.

CRC Handbook of Chemistry and Physics, Boca Raton, FL, pp. D196-D203, 1986.

Döbele, H. F., and B. Rückle. Plasma Physics, vol. 24, p. 1419, 1982.

Döbele, H. F., and B. Rückle. Journal of Nuclear Materials, vols. 111 and 112, p. 102, 1992.

Dobratz, B. M. "Properties of Chemical Explosives and Explosive Simulants." <u>LLNL Explosives</u> Handbook, March 16, 1981.

Fainberg, A. Science, vol. 255, p. 1531, 1992.

Haung, S. D., L. Kolaitis, and D. M. Ludman. Applied Spectroscopy, vol. 41, p. 1371, 1987.

Imasaka, T., T. Okamura, and N. Ishibashi. Analytical Chemistry, vol. 58, p. 2152, 1986.

Karataev, V. I., B. A. Mamyrin, and D. V. Shmikk. Sov. Phys. Tech. Phys., vol. 16, p. 1177, 1972.

Lee, S. C., B. J. Staton, B. A. Eldridge, and E. L. Wehry. Analytical Chemistry, vol. 64, p. 266, 1992.

Lemire, G. W., J. B. Simeonsson, and R. C. Sausa. Analytical Chemistry, vol. 65, p. 529, 1993.

Marshall, A., A. Clark, K. W. D. Ledingham, and R. P. Singhal. <u>International Journal of Mass Spectrom.</u> <u>Ion Process</u>, vol. 112, p. 273, 1992.

Moss, D. B., K. A. Trentelman, and P. L. Houston. <u>Journal of Chemical Physics</u>, vol. 96, no. 1, p. 237, 1992.

Oldenborg, R. C., and S. L. Baughcum. Analytical Chemistry, vol. 58, p. 1430, 1986.

Reutter, D. J., R. C. Buechele, and T. L. Rudolph. Analytical Chemistry, vol. 55, p. 1468A, 1983.

Robie, D. C., J. D. Buck, and W. K. Bishel. Applied Optics, vol. 29, p. 3961, 1990.

Rodgers, M. O., K. Asai, and D. D. Davis. Applied Optics, vol. 19, p. 3597, 1980.

Sausa, R. C., A. J. Alfano, and A. W. Miziolek. Applied Optics, vol. 26, p. 3588, 1987.

- Schendel, J., R. Hohmann, and E. L. Wehry. Applied Spectroscopy, vol. 41, p. 640, 1987.
- Schendel, J. S., R. E. Stickel, C. A. van Dijk, S. T. Sandholm, D. D. Davis, and J. D. Bradshaw. Applied Optics, vol. 29, p. 4924, 1990.
- Schendel, J., and E. L. Wehry. Analytical Chemistry, vol. 60, p. 1759, 1988.
- Silverstein, R. M., G. C. Bassler, and T. C. Morrill. <u>Spectrometric Identification of Organic Compounds</u>, 5th edition, New York: John Wiley and Sons, 1991.
- Smit, K. J. Journal of Energetic Materials, vol. 9, p. 81, 1991.
- Wiley, W. C., and I. H. McLaren. Rev. Sci. Instruments, vol. 26, p. 1150, 1955.
- Wodtke, A. M., L. Huwel, H. Schluter, G. Meijer, P. Anderson, and H. Voges. Optics Letters, vol. 13, p. 910, 1988.

NO. OF		NO. OF	
COPIES	ORGANIZATION	COPIES	ORGANIZATION
2	ADMINISTRATOR	1	COMMANDER
2	DEFENSE TECHNICAL INFO CENTER	•	US ARMY MISSILE COMMAND
	ATTN: DTIC-DDA		ATTN: AMSMI-RD-CS-R (DOC)
	CAMERON STATION		REDSTONE ARSENAL AL 35898-5010
	ALEXANDRIA VA 22304-6145		
		1	COMMANDER
1	COMMANDER		US ARMY TANK-AUTOMOTIVE COMMAND
	US ARMY MATERIEL COMMAND		ATTN: AMSTA-JSK (ARMOR ENG BR)
	ATTN: AMCAM		WARREN MI 48397-5000
	5001 EISENHOWER AVE		
	ALEXANDRIA VA 22333-0001	1	DIRECTOR
			US ARMY TRADOC ANALYSIS COMMAND
_	DIRECTOR		ATTN: ATRC-WSR
	US ARMY RESEARCH LABORATORY		WSMR NM 88002-5502
	ATTN: AMSRL-OP-SD-TA/	_	
	RECORDS MANAGEMENT	1	COMMANDANT
	2800 POWDER MILL RD		US ARMY INFANTRY SCHOOL
	ADELPHI MD 20783-1145		ATTN: ATSH-WCB-O
2	DIDECTOR		FORT BENNING GA 31905-5000
	DIRECTOR US ARMY RESEARCH LABORATORY		
	ATTN: AMSRL-OP-SD-TL/		ABERDEEN PROVING GROUND
	TECHNICAL LIBRARY		ABERDEEN I ROVENO GROUND
	2800 POWDER MILL RD	2	DIR, USAMSAA
	ADELPHI MD 20783-1145	<u>-</u>	ATTN: AMXSY-D
			AMXSY-MP/H COHEN
1	DIRECTOR		·
	US ARMY RESEARCH LABORATORY	1	CDR, USATECOM
	ATTN: AMSRL-OP-SD-TP/		ATTN: AMSTE-TC
	TECH PUBLISHING BRANCH		
	2800 POWDER MILL RD	1	DIR, USAERDEC
	ADELPHI MD 20783-1145		ATTN: SCBRD-RT
•	COLUMNIE		ODD HIGA ODDOOM
	COMMANDER US ARMY ARDEC	1	CDR, USACBDCOM ATTN: AMSCB-CII
	ATTN: SMCAR-TDC		ATTN: AMSCB-CII
	PICATINNY ARSENAL NJ 07806-5000	1	DIR, USARL
	FICATION I ARSENAL IN 07000-5000	1	ATTN: AMSRL-SL-I
1	DIRECTOR		ATTIV. AMBRE-SE-I
	BENET LABORATORIES	5	DIR, USARL
	ATTN: SMCAR-CCB-TL		ATTN: AMSRL-OP-AP-L
	WATERVLIET NY 12189-4050		
1	DIRECTOR		
	US ARMY ADVANCED SYSTEMS		
	RESEARCH AND ANALYSIS OFFICE		
	ATTN: AMSAT-R-NR/MS 219-1		
	AMES RESEARCH CENTER		
	MOFFETT FIELD CA 94035-1000		

NO. OF NO. OF **COPIES ORGANIZATION** COPIES ORGANIZATION 1 HODA COMMANDER ATTN SARD TT DR F MILTON ATTN SMCAR AEE BR L HARRIS WASH DC 20310-0103 **USARDEC** PCTNY ARSNL NJ 07806-5000 HODA 1 ATTN SARD TT MR J APPEL COMMANDER WASH DC 20310-0103 ATTN AMSMI RD PR E A R MAYKUT AMSMI RD PR P R BETTS HODA 1 US ARMY MISSILE COMMAND ATTN SARD TR MS K KOMINOS REDSTONE ARSNL AL WASH DC 20310 0103 1 OFFICE OF NAVAL RSCH DEPT OF THE NAVY 1 HODA ATTN R S MILLER CODE 432 ATTN SARD TR DR R CHAIT 800 N OUINCY ST WASH DC 20310 0103 **ARLINGTON VA 22217** 1 HODA COMMANDER ATTN OASA RDA DR C H CHURCH ATTN J RAMNARACE AIR 54111C PENTAGON RM 3E486 NAVAL AIR SYSTEMS COMMAND WASH DC 20310-0103 WASH DC 20360 **COMMANDER** 2 **COMMANDER** ATTN R GHIRARDELLI ATTN R BERNECKER R 13 D MANN G B WILMOT R 16 R SINGLETON NAVAL SURFACE WARFARE CTR R SHAW SLVR SPRNG MD 20903-5000 US ARMY RSRCH OFFICE PO BOX 12211 COMMANDER RSRCH TRIGL PK NC 27709-2211 ATTN M C LIN J MCDONALD DIRECTOR 1 E ORAN ATTN AMXRO MCS K CLARK J SHNUR US ARMY RSRCH OFFICE R J DOYLE CODE 6110 PO BOX 12211 NAVAL RSCH LAB RSRCH TRIGL PK NC 27709-2211 WASH DC 20375 DIRECTOR 2 COMMANDER ATTN AMXRO RT IP LIBRARY ATTN T BOGGS CODE 388 **SERVICES** T PARR CODE 3895 US ARMY RSRCH OFFICE NAVAL WEAPONS CTR PO BOX 12211 CHINA LAKE CA 93555-6001 RSRCH TRIGL PK NC 27709-2211 **SUPERINTENDENT** COMMANDER ATTN D W NETZER ATTN SMCAR AEE B D S DOWNS NAVAL POSTGRADUATE SCHOOL USARDEC **DEPT OF AERONAUTICS** PCTNY ARSNL NJ 07806-5000

COMMANDER

USARDEC

ATTN SMCAR AEE J A LANNON

PCTNY ARSNL NJ 07806-5000

MONTEREY CA 93940

NO. OF COPIES	ORGANIZATION	NO. OF COPIES	ORGANIZATION
3	AL LSCF ATTN R CORLEY R GEISLER	1	NATL SCIENCE FOUNDATION ATTN A B HARVEY WASH DC 20550
	J LEVINE EDWARDS AFB CA 93523-5000	2	PRINCETON COMBUSTION RSRCH LAB INC ATTN N A MESSINA
1	AFOSR ATTN J M TISHKOFF BOLLING AIR FORCE BASE WASH DC 20332		M SUMMERFIELD PRINCETON CORPORATE PLAZA BLDG IV STE 119 11 DEERPARK DR MONMOUTH JUNCTION NJ 08852
1	OSD SDIO IST ATTN L CAVENY PENTAGON WASH DC 20301-7100	3	DIRECTOR ATTN S JOHNSTON P MATTERN D STEPHENSON
1	COMMANDANT ATTN ATSF TSM CN USAFAS FT SILL OK 73503-5600	1	SANDIA NATL LAB DIV 8354 LIVERMORE CA 94550 BRIGHAM YOUNG UNIV
1	UNIV OF DAYTON RSRCH INSTITUTE ATTN D CAMPBELL AL PAP		ATTN M W BECKSTEAD DEPT OF CHEMICAL ENGRG PROVO UT 84058
_	EDWARDS AFB CA 93523	1	CA INSTITUTE OF TECH JET PROPULSION LAB ATTN L STRAND MS 125 224
1	NASA ATTN G B NORTHAM MS 168 LANGLEY RSCH CTR		4800 OAK GROVE DR PASADENA CA 91109
	LANGLEY STATION HAMPTON VA 23365	1	CALIFORNIA INSTITUTE OF TECHNOLOGY ATTN F E C CULICK MC 301 46 204 KARMAN LAB
4	NATIONAL BUREAU OF STANDARDS ATTN J HASTIE		PASADENA CA 91125
	M JACOX T KASHIWAGI H SEMERJIAN US DEPT OF COMMERCE WASH DC 20234	1	UNIV OF CALIFORNIA ATTN LOS ALAMOS SCIENTIFIC LAB PO BOX 1663 MAIL STOP B216 LOS ALAMOS NM 87545
2	DIRECTOR ATTN C WESTBROOK W TAO MS L 282 LAWRENCE LIVERMORE NATL LAB PO BOX 808		UNIV OF CALIFORNIA BERKELEY ATTN C BRADLEY MOORE CHEMISTRY DEPT 211 LEWIS HALL BERKELEY CA 94720
	LIVERMORE CA 94550		UNIV OF CALIFORNIA SAN DIEGO ATTN F A WILLIAMS
1	DIRECTOR ATTN B NICHOLS T7 MS B284 LOS ALAMOS NATL LAB PO BOX 1663 LOS ALAMOS NM 87545		AMES B010 LA JOLLA CA 92093

NO. OF		NO. OF	
COPIES	ORGANIZATION	COPIES	ORGANIZATION
2	UNIV OF CALIFORNIA SANTA BARBARA	1	THE JOHNS HOPKINS UNIV
	ATTN K SCHOFIELD		ATTN T W CHRISTIAN
	M STEINBERG		CHEMICAL PROPULSION
	QUANTUM INSTITUTE		INFORMATION AGENCY
	SANTA BARBARA CA 93106		10630 LITTLE PATUXENT PKWY
			STE 202
1	UNIV OF COLORADO AT BOULDER		COLUMBIA MD 21044 3200
	ATTN J DAILY		
	ENGRG CTR	1	UNIV OF MICHIGAN
	CAMPUS BOX 427		ATTN G M FAETH
	BOULDER CO 80309 0427		GAS DYNAMICS LAB
			AEROSPACE ENGRG BLDG
3	UNIV OF SOUTHERN CALIFORNIA		ANN ARBOR MI 48109 2140
	ATTN R BEAUDET	_	
	\$ BENSON	1	UNIV OF MINNESOTA
	C WITTIG		ATTN E FLETCHER
	DEPT OF CHEMISTRY		DEPT OF MECHANICAL ENGRG
	LOS ANGELES CA 90007		MINNEAPOLIS MN 55455
1	CORNELL UNIV	4	PENNSYLVANIA STATE UNIV
	ATTN T A COOL		ATTN K KUO
	DEPT OF CHEMISTRY		M MICCI
	BAKER LAB		S THYNELL
	ITHACA NY 14853		V YANG
			DEPT OF MECHANICAL ENGRG
1	UNIV OF DELAWARE		UNIV PK PA 16802
	ATTN T BRILL		
	CHEMISTRY DEPT	1	POLYTECHNIC INSTITUTE OF NY
	NEWARK DE 19711		ATTN S LEDERMAN
			GRADUATE CTR
1	UNIV OF FLORIDA		RTE 110
	ATTN J WINEFORDNER		FARMINGDALE NY 11735
	DEPT OF CHEMISTRY	•	DD DIOCTON IDIU
	GAINESVILLE FL 32611	2	PRINCETON UNIV
2	OFORGIA DISTITUTE OF TEOLDIOLOGY		ATTN K BREZINSKY
3	GEORGIA INSTITUTE OF TECHNOLOGY		I GLASSMAN FORRESTAL CAMPUS LIB
	ATTN E PRICE W C STRAHLE		PO BOX 710
			PRINCETON NJ 08540
	B T ZINN SCHOOL OF AEROSPACE ENGRG		PRINCETON NJ 06540
	ATLANTA GA 30332	1	PURDUE UNIV
	ATLANTA GA 30332		ATTN J R OSBORN
1	UNIV OF ILLINOIS		SCHOOL OF AERONAUTICS & ASTRONAUTICS
1	ATTN H KRIER		GRISSOM HALL
	DEPT OF MECH ENGRG		WEST LAFAYETTE IN 47906
	144MEB 1206 W GREEN ST		W TO I DIMITIDITE IN 41700
	URBANA IL 61801	1	PURDUE UNIV
	ORDINATE OTOOT	•	ATTN E GRANT
			DEPT OF CHEMISTRY
			NICOT I AT ANOTHER TALL ATOM

WEST LAFAYETTE IN 47906

NO. OF COPIES	ORGANIZATION	NO. OF COPIES	ORGANIZATION
2	PURDUE UNIV	1	BATTELLE
	ATTN N M LAURENDEAU		TWSTIAC
	S N B MURTHY		HUGGINS
	SCHOOL OF MECHANICAL ENGRG		505 KING AVE
	TSPC CHAFFEE HALL		COLUMBUS, OH 43201-2693
	WEST LAFAYETTE IN 47906		
		1	COHEN PROFESSIONAL SERVICES
1	RENSSELAER POLYTECHNIC INST		ATTN N S COHEN
	ATTN A FONTIJN		141 CHANNING ST
	DEPT OF CHEMICAL ENGRG		REDLANDS CA 92373
	TROY NY 12181		
		1	EXXON RSCH & ENGRG CO
1	STANFORD UNIV		ATTN A DEAN
	ATTN R HANSON		RTE 22E
	DEPT OF MECHANICAL ENGRG		ANNANDALE NJ 08801
	STANFORD CA 94305		
		1	GENERAL APPLIED SCIENCE LAB INC
1	UNIV OF TEXAS		77 RAYNOR AVE
	ATTN W GARDINER		RONKONKAMA NY 11779-6649
	DEPT OF CHEMISTRY		
	AUSTIN TX 78712	1	GENERAL ELECTRIC ORD SYSTEMS
_			ATTN J MANDZY
1	VA POLYTECHNIC INST & STATE UNIV		100 PLASTICS AVE
	ATTN J A SCHETZ		PITTSFIELD MA 01203
	BLACKSBURG VA 24061	_	
_	A DEL TER COLORIOUS ERICH DIO	1	GENERAL MOTORS RSCH LAB
1	APPLIED COMBUSTION TECH INC		ATTN T SLOANE
	ATTN A M VARNEY		PHYSICAL CHEMISTRY DEPT
	PO BOX 607885		WARREN MI 48090-9055
	ORLANDO FL 32860	•	HEDOLII EC DIO
•	ADDITION ACCOLLANGE DEVICENCE	2	HERCULES INC
2	APPLIED MECHANICS REVIEWS		ATTN W B WALKUP
	ATTN R E WHITE		E A YOUNT
	A B WENZEL		ALLEGHENY BALLISTICS LAB
	THE AMERICAN SOCIETY OF MECH ENGRG		ROCKET CTR WV 26726
	345 E 47TH ST	•	HEDOLE EC DIO
	NEW YORK NY 10017	1	HERCULES INC
1	ATT ANTIC DOCULOODD		ATTN R V CARTWRIGHT
1	ATLANTIC RSCH CORP ATTN R H W WAESCHE		100 HOWARD BLVD KENVIL NJ 07847
	7511 WELLINGTON RD		KENVIL NJ 0/64/
•	GAINESVILLE VA 22065	1	ALLIANT TECHSYSTEMS INC
	GAINES VILLE VA 22003	1	ATTN D E BRODEN
1	TEXTRON DEFENSE SYSTEMS	•	MS MN50 2000
	ATTN A PATRICK		MARINE SYSTEMS GROUP
	2385 REVERE BEACH PKWY		600 2ND ST NE
			HOPKINS MN 55343
	EVERETT MA 02149-5900		CHCCC MMI CANTAIOTI

NO. OF COPIES	ORGANIZATION	NO. OF COPIES	ORGANIZATION
1	ALLIANT TECHSYSTEMS INC ATTN R E TOMPKINS MN 11 2720 600 SECOND ST N HOPKINS MN 55343	3	SRI INTERNATIONAL ATTN G SMITH D CROSLEY D GOLDEN 333 RAVENSWOOD AVE MENLO PK CA 94025
1	IBM CORPORATION ATTN A C TAM RSRCH DIV 5600 COTTLE RD SAN JOSE CA 95193	1	STEVENS INSTITUTE OF TECH ATTN R MCALEVY III DAVIDSON LAB HOBOKEN NJ 07030
1	IIT RSRCH INSTITUTE ATTN R F REMALY 10 W 35TH ST CHICAGO IL 60616	1	SVERDRUP TECH INC ATTN R J LOCKE MS SVR 2 LERC GROUP 2001 AEROSPACE PKWY BROOK PK OH 44142
1	LOCKHEED MISSILES & SPACE CO ATTN GEORGE LO DEPT 52 35 B204 2 3251 HANOVER ST PALO ALTO CA 94304	1	SVERDRUP TECH INC ATTN J DEUR 2001 AEROSPACE PKWY BROOK PK OH 44142
1	OLIN ORDNANCE ATTN V MCDONALD LIB PO BOX 222 ST MARKS FL 32355-0222	3	THIOKOL CORPORATION ATTN R BIDDLE R WILLER TECH LIB ELKTON DIV
1	PAUL GOUGH ASSOCIATES INC ATTN P S GOUGH 1048 S ST PORTSMOUTH NH 03801-5423	3	PO BOX 241 ELKTON MD 21921 THIOKOL CORP
1	HUGHES AIRCRAFT CO ATTN T E WARD 8433 FALLBROOK AVE CANOGA PK CA 91303		ATTN S J BENNETT WASATCH DIV PO BOX 524 BRIGHAM CITY UT 84302
1	ROCKWELL INTERNATIONAL CORP ATTN J E FLANAGAN HB02 ROCKETDYNE DIV	1	UNITED TECH RSCH CTR ATTN A C ECKBRETH E HARTFORD CT 06108
	6633 CANOGA AVE CANOGA PK CA 91304	1 .	UNITED TECH CORP ATTN R R MILLER CHEMICAL SYSTEM DIV
1	SCIENCE APPLICATIONS INC ATTN R B EDELMAN 23146 CUMORAH CREST WOODLAND HILLS CA 91364	1	PO BOX 49028 SAN JOSE CA 95161-9028 UNIVERSAL PROPULSION CO
		-	ATTN H J MCSPADDEN 25401 N CENTRAL AVE PHOENIX AZ 85027-7837

NO. OF NO. OF COPIES ORGANIZATION COPIES ORGANIZATION ABERDEEN PROVING GROUND VERITAY TECH INC 1 ATTN E B FISHER DIR USARL **4845 MILLERSPORT HWY** 36 ATTN AMSRL PFD E AMHERST NY 14051-0305 A W HORST R A FIFER 1 FREEDMAN ASSOCIATES G F ADAMS ATTN E FREEDMAN 2411 DIANA RD W R ANDERSON R A BEYER **BALTIMORE MD 21209-1525** S W BUNTE 6 **ALLIANT TECHSYSTEMS** C F CHABALOWSKI ATTN J BODE K P MCNEILL-BOONSTOPPEL A COHEN C CANDLAND L OSGOOD R CUMPTON R DANIEL R BURETTA D DEVYNCK R BECKER N F FELL M SWENSON 600 SECOND ST NE B E FORCH HOPKINS MN 55343 J M HEIMERL A J KOTLAR US ARMY BENET LAB M R MANAA 1 W F MCBRATNEY ATTN SAM SOPOK K L MCNESBY SMCAR CCB B S V MEDLIN **WATERVALIET NY 12189** M S MILLER A W MIZIOLEK S H MODIANO J B MORRIS J E NEWBERRY S A NEWTON R PASTEL R A PESCE RODRIGUEZ B M RICE R C SAUSA M A SCHROEDER J A VANDERHOFF M WENSING A WHREN J M WIDDER

C WILLIAMSON

USER EVALUATION SHEET/CHANGE OF ADDRESS

This Laboratory undertakes a continuing effort to improve the quality of the reports it publishes. Your

comments/answe	rs to the items/questions below wi	l aid us in our efforts.
1. ARL Report N	umber ARL-TR-628	Date of Report November 1994
2. Date Report Re	ceived	
which the report v	vill be used.)	purpose, related project, or other area of interest for
4. Specifically,	- ·	formation source, design data, procedure, source of
operating costs av	voided, or efficiencies achieved, etc	atitative savings as far as man-hours or dollars saved? If so, please elaborate.
	zation, technical content, format, et	d be changed to improve future reports? (Indicat
	Organization	
CURRENT	Name	
ADDRESS	Street or P.O. Box No.	
	City, State, Zip Code	
	Change of Address or Address Cond or Incorrect address below.	rection, please provide the Current or Correct addres
	Organization	
OLD	Name	
ADDRESS	Street or P.O. Box No.	
	City, State, Zip Code	·
	(Remove this sheet fold as in	licated tane closed and mail \

(DO NOT STAPLE)



OFFICIAL BUSINESS



BUSINESS REPLY MAIL FIRST CLASS PERMIT NO 0001, APG, MD

Postage will be paid by addressee

Director
U.S. Army Research Laboratory
ATTN: AMSRL-OP-AP-L
Aberdeen Proving Ground, MD 21005-5066

NO POSTAGE
NECESSARY
IF MAILED
IN THE
UNITED STATES